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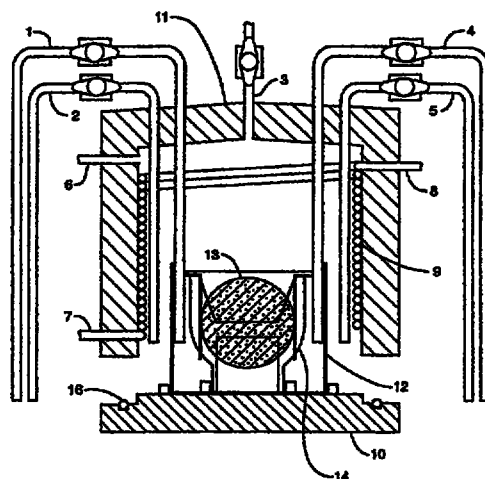
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(54) Title: SUPERCRITICAL FLUID DRYING SYSTEM



(57) Abstract: A method and apparatus for fabricating and drying wafers (13), including micro-electronics mechanical systems (MEMS) structures, in a second supercritical processing fluid environment. The apparatus utilizes an inverted pressure vessel (11) connected to a supercritical processing fluid supply and recovery system, with an internal heat exchanger (9) connected to external heating and cooling sources, which is closed with a vertically movable base (10). A wafer cassette (14) configured for supporting multiple wafers (13) is submerged in a first processing fluid within a container (12), which is installed on the base plate (10) for insertion onto the pressure vessel (11). Vessel (11) inlet (2) and outlet (5) tubes extend vertically downward from the ceiling of the pressure vessel (11) to nearly the base plate (10). Container (12) inlet (1) and outlet (4) tubes extend vertically down from the ceiling of the pressure vessel (11) to the inside of the container (12) and nearly to the bottom of the container (12).



For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.